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Tel: (713) 228-8600
Fax: (713) 228-8778**FACSIMILE TRANSMITTAL SHEET**

DATE: July 19, 2005

FILE NUMBER: 03850/010001

TO: John R. Lee
Supervisory Patent Examiner

FAX NUMBER: 703-872-9306

FROM: Jonathan P. Osha

PAGES INCLUDING COVER: 3

RE: Agenda for July 21, 2005, Interview
re U.S. Patent Application Serial No. 09/934,262☐ URGENT ☐ FOR REVIEW ☐ PLEASE COMMENT ☐ PLEASE REPLY ☐ PLEASE RECYCLE

NOTES/COMMENTS:

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Suite 2800
1221 McKinney Street
Houston, Texas 77010

OSHA • LIANG LLP

Telephone: 713.228.8600
Facsimile: 713.228.8778
firm@oshaliang.com
www.oshaliang.com

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Via Facsimile 703-872-9306

Mr. John R. Lee
Supervisory Patent Examiner
Art Unit 2881
U.S. Patent and Trademark Office
P.O. Box 1450
Alexandria, VA 22313-1450

AGENDA FOR INTERVIEW
JULY 21, 2005, 2:00 P.M.

Re: U.S. Patent Application No. 09/934,262
APPARATUS AND METHOD FOR EXPOSING A RADIATION
SENSITIVE LAYER BY MEANS OF CHARGED PARTICLES AS
WELL AS A MASK FOR THIS PURPOSE
Inventor(s): Oliver Kienzle et al.
Filing Date: August 21, 2001
Your Ref.: Z8435-US; Our Ref.: 03850/010001

Dear Mr. Lee:

Thank you for your kind agreement to conduct a personal interview in the above-captioned case during Examiner Kiet Nguyen's absence. I confirm attendance at the scheduled interview at 2:00 p.m. on July 21, 2005, on behalf of the Applicant.

The Applicant proposes the following as a brief agenda of the interview:

1. Brief Summary of Invention.

The Applicant will briefly explain the invention with reference to the embodiment described in Figures 4-6. Particularly, the Applicant will explain how deviations from the predetermined scan path are reduced by detecting charged particles impinging upon at least one mark region on the mask during scanning.



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Mr. John R. Lee

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2. Discussion of Rejection Under 35 U.S.C. § 112, ¶ 1

The Applicant will briefly explain support for the limitation "a sensor for detecting, concurrently with the imaging of the pattern of the mask onto the substrate, a number of the charged particles impinging on the at least one mark region provided on the mask," particularly with reference to Figures 1 and 4 and paragraphs 0027, 0028 and 0049 of the specification. A written explanation of support for this limitation may be found in the Response dated February 25, 2005, under the heading "Rejection Under 35 U.S.C. § 112, 1st Paragraph" beginning on page 7 thereof. The Applicant will request the Supervising Primary Examiner's assistance in understanding the meaning and relevance of the sole statement in support of this rejection, namely, "Therefore, the Examiner don't [sic] know how is [sic] the sensitive layer of the substrate damaged when the charged particle beam is uncorrected?" (Office Action of April 12, 2005, p. 2)

3. Rejection Under 35 U.S.C. § 102(a)

The Applicant will briefly explain how the claimed invention, which recites a system wherein scanned beam deviations are corrected during scanning, differs from a pre-scan system such as that disclosed by Yahiro et al. It is noted that substantive arguments distinguishing the claimed invention from Yahiro et al. were presented at pp. 8-11 of the Response filed September 13, 2004, and were reiterated at pp. 9-10 of the Response filed February 25, 2005. The Examiner has not yet provided a substantive reply to those arguments. Accordingly, the Applicant seeks the Supervisory Primary Examiner's assistance in understanding the Examiner's position as to this rejection, so that a suitable resolution can be reached without further delay.

Respectfully submitted,

A handwritten signature in black ink, appearing to read 'Jonathan P. Osha'.

Jonathan P. Osha

JPO/dmb